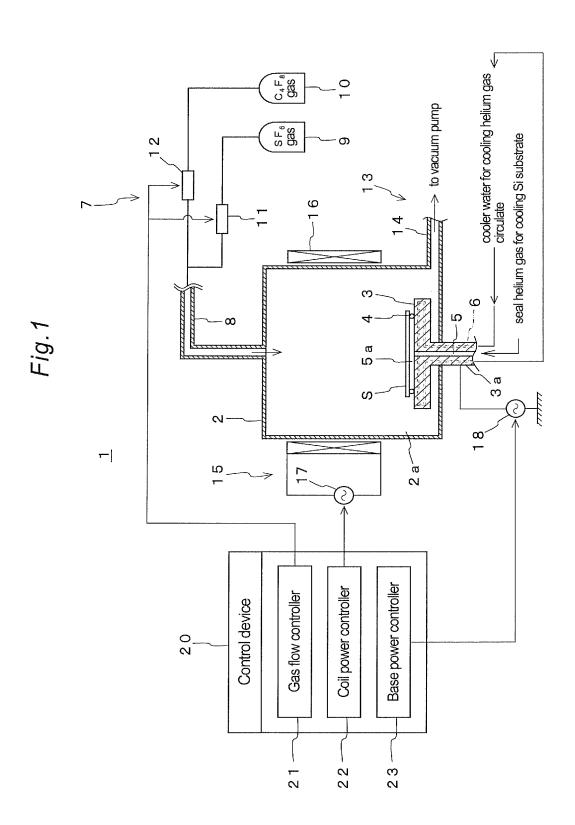
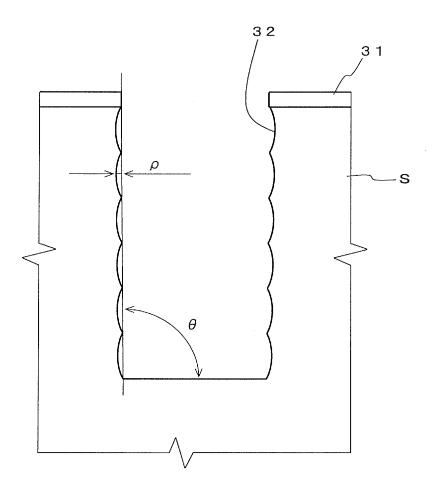
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Fig.3



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Fig.4

	Embodiment	Comparative Example
Etching rate (µm/min)	3.7	3.4
Mask selection ratio	140	104
Unevenness ρ (nm)	160	250
Hole sidewall angle (degrees)	90.2	90.5